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In re Patent Application:

Inventor: Michael D. WELCH et al.

Serial No.: Unknown. (Continuation of SN 09/711,191.)

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Title: Double Slit Valve Doors for Plasma Processing

Prior Examiner: Bueker, R.

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Mail Stop PATENT APPLICATION
Commissioner for Patents
P.O. Box 1450
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PRELIMINARY AMENDMENT

Please amend the concurrently filed continuation patent application as follows:

In the Claims

Cancel claims 1–30.

Insert the following new claims 31–43:

1 31. A chamber liner apparatus for covering a portion of a cylindrical side wall of a plasma chamber,
2 comprising:

3 a cylindrical liner having cylindrical inner and outer surfaces;
4 wherein the liner includes an aperture extending between said inner and outer surfaces;
5 wherein the outer surface of the liner includes a recess contiguous with the aperture; and
6 wherein the recess does not extend through the liner to the inner surface of the liner.

1 32. Apparatus according to claim 31, wherein:

2 the aperture and the recess are each characterized by a respective circumferential width
3 dimension along the circumference of the liner; and
4 the recess has a circumferential width equal to or greater than the circumferential width of the
5 aperture.